## **Amendments to the Specification:**

Replace the paragraph on Page 6, lines 17-19 with the following:

Figure 1 The Drawing is a schematic view of one embodiment of the invention showing a dual reaction zone system and an optional assembly for treating impurity gas with a fluorine gas treating assembly.

Replace the paragraph on page 10, lines 1-14 with the following:

Referring to Figure 1 the Drawing, there is shown a nitrogen trifluoride production system 2 having a first reaction zone 4 and a second reaction zone 6. In accordance with the present invention, the first reaction zone 4 is typically in the form of one or more conduits or channels having a relatively high aspect ratio typically within the range of from about 5 to 150, preferably from about 10 to 100. The second reaction zone typically has a low aspect ration of up to 5, typically about 1. The first reaction zone 4 has a relatively low power input of typically less than about 1000 Watts per cubic meter NH<sub>4</sub>F(HF)<sub>x</sub>, preferably less than 500 watts/m³ and makes use of a static mixing of the reactants through the use of static mixing elements which are identified by the numeral 14 and include static mixing elements in the conduit 40. Static mixing elements including heat exchange capability are available under the trademark Kenics from Chemineer, Inc. The NH<sub>4</sub>F(HF)<sub>x</sub> flow flux in the first reaction zone 4 is typically in the range of from 30 to 300 cm³/cm²/second, preferably from 50 to 200 cm³/cm²/second.